	Hits	Search Text	DBs
24	133	((substrate or wafer or device or workpiece) same (support$3 or stage or hold$3 or pedestal) same (resist or photoresist or photocur$4) same (irradiat$4 or illuminat$4 or (UV near9 source) or excimer or KrF or ArF or e$3beam or (electron near4 beam) or EUV or DUV or VUV)) and pattern$3 and ((pattern$6 near5 device) or mask$4 or reticle or photo$4mask or (phase near5 shift$4 near5 mask)) and (($4lithograph$6 or photolithograph$6) same (beam or laser or ion$8assist$5 or irradiat$4 or (ion near9 beam)) same (nitrogen or hydrogen or Ar or Ne or Kr or He or alkane or hydrocarbon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	49	((substrate or wafer or device or workpiece) same (support$3 or stage or hold$3 or pedestal) same (resist or photoresist or photocur$4) same (irradiat$4 or illuminat$4 or (UV near9 source) or excimer or KrF or ArF or e$3beam or (electron near4 beam) or EUV or DUV or VUV or laser)) and pattern$3 and (((pattern$6 near5 device) or mask$4 or reticle) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same (nitrogen or hydrogen or Ar or Ne or Kr or He or alkane or hydrocarbon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB